

**IN THE CLAIMS**

This listing of claims replaces all prior listings:

1. (Currently Amended) A Method method of manufacturing a diffusing reflector comprising the processes of:

preparing a substrate;

forming a first resin film having photosensitivity on said substrate;

providing a gathering of pillar-shaped bodies isolated from each other through patterning of said resin film with photolithography;

deforming gently said pillar-shaped bodies through a reflow;

forming an uneven surface layer having the maximum inclination angle of under 12<sup>0</sup> by coating with a thin layer of a second resin said gently deformed pillar-shaped bodies and;

covering with the second resin open flat spaces located between said isolated pillar-shaped bodies to form one concave gap between two adjacent isolated pillar-shaped bodies so that upper end portions of said two adjacent isolated pillar-shaped bodies are higher than a lower end portion of said one concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on said substrate; and

forming a metal film on said uneven surface layer,

wherein,

said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight lines providing a gap between thereby formed polygonal pillar-shaped bodies, and

said gap having a size equal to about a minimum resolution of said photolithography.

2. (Currently Amended) The Method method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about 10<sup>0</sup>.

3. (Cancelled)

4. (Currently Amended) The Method method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is a heat treatment under the temperature of about 220<sup>0</sup>C.

5. (Currently Amended) The Method method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated from each other by the divided patterning of said first resin film by said photolithography is provided.

6. (Cancelled)